

A marked up version showing amendments to any claims being changed is provided in one or more accompanying pages separate from this amendment in accordance with 37 C.F.R. § 1.121(c)(1)(ii). Any claim not accompanied by a marked up version has not been changed relative to the immediate prior version, except that marked up versions are not being supplied for any added claim or canceled claim.

B1 <sup>1</sup>  
~~31.~~ (Once amended) A layer comprising high purity tantalum, less than about 500 ppm, by weight, total metallic impurities, less than 20 ppm, by weight, total of tungsten and molybdenum, and less than 50 ppm, by weight, niobium.

<sup>3</sup> ~~34.~~ (Once amended) The layer of claim <sup>1</sup>~~31~~ comprising less than about 10 ppmw niobium.

B2 <sup>4</sup>  
~~36.~~ (Once amended) A sputtering target blank comprising tantalum, less than 500 ppm by weight (ppmw) total metallic impurities, less than 5 ppmw total of molybdenum and tungsten, less than about 100 ppmw oxygen, and less than 50 ppmw niobium.

<sup>5</sup> ~~38.~~ (Once amended) The blank of claim <sup>4</sup>~~36~~ comprising less than 10 ppmw niobium.

<sup>20</sup> ~~54.~~ (new) A tantalum sputtering target blank comprising tantalum and less than 5 ppm by weight (ppmw) molybdenum or tungsten and less than 3 ppmw niobium.

B3 <sup>21</sup>  
~~55.~~ (new) The blank of claim <sup>20</sup>~~54~~ comprising less than 5 ppmw molybdenum.

<sup>22</sup> ~~56.~~ (new) The blank of claim <sup>20</sup>~~54~~ comprising less than 5 ppmw tungsten.

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<sup>23</sup>  
~~57~~. (new) The blank of claim <sup>20</sup>~~54~~ comprising less than 3 ppmw molybdenum or tungsten.

<sup>24</sup>  
~~58~~. (new) The blank of claim <sup>20</sup>~~54~~ comprising at least 99.99 weight percent tantalum.

<sup>25</sup>  
~~59~~. (new) A tantalum sputtering target blank comprising tantalum, less than 5 ppmw each of molybdenum and tungsten, and less than 50 ppmw niobium.

<sup>26</sup>  
~~60~~. (new) The blank of claim <sup>25</sup>~~59~~ comprising less than 3 ppmw each of molybdenum and tungsten.

<sup>27</sup>  
~~61~~. (new) The blank of claim <sup>25</sup>~~59~~ further comprising less than 3 ppmw niobium.

<sup>28</sup>  
~~62~~. (new) The blank of claim <sup>25</sup>~~59~~ comprising at least 99.99 weight percent tantalum.

<sup>29</sup>  
~~63~~. (new) A tantalum sputtering target blank comprising tantalum and less than 50 ppmw total of molybdenum, tungsten, and niobium.

<sup>30</sup>  
~~64~~. (new) The blank of claim <sup>29</sup>~~63~~ comprising less than 20 ppmw total of molybdenum, tungsten, and niobium.

<sup>31</sup>  
~~65~~. (new) The blank of claim <sup>29</sup>~~63~~ comprising less than 10 ppmw total of molybdenum, tungsten, and niobium.

<sup>32</sup>  
~~66~~. (new) The blank of claim <sup>29</sup>~~63~~ comprising less than 5 ppmw total of molybdenum, tungsten, and niobium.

<sup>33</sup>  
~~67~~. (new) A sputtering target comprising the blank of claim <sup>26</sup>~~54~~.

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68. (new) A sputtering target comprising the blank of claim 58.

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69. (new) A sputtering target comprising the blank of claim 63.

36

70. (new) A material comprising tantalum, at least the tantalum being sputter deposited from the blank of claim 67.

31

71. (new) A material comprising tantalum, at least the tantalum being sputter deposited from the blank of claim 68.

38

72. (new) A material comprising tantalum, at least the tantalum being sputter deposited from the blank of claim 69.

39

73. (new) A tantalum material comprising tantalum and less than 5 ppmw molybdenum or tungsten and less than 3 ppmw niobium.

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74. (new) A tantalum material comprising tantalum, less than 5 ppmw each of molybdenum and tungsten, and less than 50 ppmw niobium.

41

75. (new) A tantalum material comprising tantalum and less than 50 ppmw total of molybdenum, tungsten, and niobium.

42

76. (new) A tantalum material sputtering precursor comprising tantalum and less than 5 ppmw molybdenum or tungsten and less than 3 ppw niobium.

43

77. (new) A tantalum material sputtering precursor comprising tantalum, less than 5ppmw each of molybdenum and tungsten, and less than 50 ppmw niobium.

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7~~6~~. (new) A tantalum material sputtering precursor comprising tantalum and less than 50 ppmw total of molybdenum, tungsten, and niobium.

45

7~~6~~. (new) Sputtered tantalum material comprising tantalum and less than 5 ppmw molybdenum or tungsten and less than 3 ppw niobium.

46

8~~6~~. (new) Sputtered tantalum material comprising tantalum, less than 5ppmw each of molybdenum and tungsten, and less than 50 ppmw niobium.

47

8~~6~~. (new) Sputtered tantalum material comprising tantalum and less than 50 ppmw total of molybdenum, tungsten, and niobium.

48

8~~6~~. (new) Deposited tantalum material comprising tantalum and less than 5 ppmw molybdenum or tungsten and less than 3 ppw niobium.

49

8~~6~~. (new) Deposited tantalum material comprising tantalum, less than 5ppmw each of molybdenum and tungsten, and less than 50 ppmw niobium.

50

8~~6~~. (new) Deposited tantalum material comprising tantalum and less than 50 ppmw total of molybdenum, tungsten, and niobium.

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